	Application No.	Applicant(s)	
Notice of Allowability	10/708,746	CHIDAMBARRAO ET AL	
	Examiner	Art Unit	
	Shouxiang Hu	2811	
The MAILING DATE of this communication apperall claims being allowable, PROSECUTION ON THE MERITS IS (herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT Rig	(OR REMAINS) CLOSED in to other appropriate commun GHTS. This application is suluded MPEP 1308.	his application. If not included ication will be mailed in due cour	se. THIS
1. This communication is responsive to <u>09-03-2004 Amendment</u>	<u>ent</u> .		
2. \boxtimes The allowed claim(s) is/are <u>1-13</u> .			
3. $igotimes$ The drawings filed on 23 March 2004 are accepted by the E	Examiner.		
4. Acknowledgment is made of a claim for foreign priority un a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have 4. Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" of noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 5. A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which give of including changes required by the Notice of Draftspers 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner's Paper No./Mail Date Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the deposit of the properties of the priority documents and the deposit of the priority documents and the priority documents have a content and the priority documents and the priority documents have a content and the priority documents have a cont	been received. been received in Application cuments have been received in Application of this communication to file a ENT of this application. Itted. Note the attached EXAM is reason(s) why the oath or of the submitted. on's Patent Drawing Review (as Amendment / Comment or in the header according to 37 CFR is it of BIOLOGICAL MATER	No In this national stage application of the national stage application of the complying with the require of the Office action of the Office action of the Market (not the back 1.121(d). RIAL must be submitted. Note	ments CE OF
Attachment(s) 1. ⊠ Notice of References Cited (PTO-892)	5. Notice of Info	rmal Patent Application (PTO-15	2)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. M Interview Sun		
 Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date <u>20040323</u> 		ail Date <u>20041124</u> . mendment/Comment	
4. Examiner's Comment Regarding Requirement for Deposit	· -	tatement of Reasons for Allowan	ce
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EXAMINER'S AMENDMENT

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in telephone interviews with Eric W. Petraske (RN: 28,459) on November 17, 2004, and with Todd Li (RN: 45,554) on November 24, 2004

The application has been amended as follows:

IN THE CLAIMS

Claims 14-20 are canceled.

In claim 1, line 14, delete the term of "outside said transistor body and".

Allowable Subject Matter

Claims 1-13 are allowed.

Reasons for Allowance

The following is an examiner's statement of reasons for allowance: Prior art does not teach or render obvious a method for forming an N-type transistor as defined in the above allowed claims, comprising particularly the steps of: forming a pair of temporary

layer.

dielectric spacers on the sides of the gate electrode; removing a portion of a strained silicon layer outside the transistor body and below the pair of temporary spacers by a substantially non-directional process, which naturally forms an undercut beneath the temporally spacers, leaving a buffer portion of strained silicon in the strained silicon layer and forming a first S/D aperture outside the buffer portion; forming an electrode layer of silicon in the first S/D aperture, making mechanical and electrical contact with the transistor body and with a portion of an underlying SiGe support layer; forming transition doped areas between the transistor body and electrode areas in the electrode

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. References A-H are cited as being related to a method for forming a transistor structure involving spacers.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Shouxiang Hu whose telephone number is 571-272-1654. The examiner can normally be reached on Monday through Thursday, 7:30 AM to 6:00 PM.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Eddie C. Lee can be reached on 571-272-1732. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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